- 3  $[R"NH]^{-}$ , carboxamides  $[R"C(O)NR"]^{-}$ , carbanions  $[R"]^{-}$ , carbonate  $[CO_3]^{-2}$ , sulfate  $[SO_4]^{-2}$ ,
- 4 phosphate  $[PO_4]^{-3}$ , biphosphate  $[HPO_4]^{-2}$ , phosphorus ylides  $[R''_4P]^{-1}$ , nitrate  $[NO_3]^{-1}$ , borate
- 5 [B(OH)<sub>4</sub>], cyanate [OCN], fluoride [F], hypochlorite [OCl], silicate [SiO<sub>4</sub>], stannate [SnO<sub>4</sub>],
- 6 basic metal oxides comprising Al<sub>2</sub>O<sub>3</sub>, CaO, and ZnO, amines R"<sub>3</sub>N and amine oxides R"<sub>3</sub>NO,
- and organometallics comprising R"Li, R"<sub>2</sub>Zn, R"<sub>2</sub>Mg, and R"MgX', where R" represents an
- 8 organic substituent and multiple organic substituents need not be identical, and X' represents an
- 9 inorganic substituent.
- 1 32. (Once amended) The process of claim 31, wherein the co-reagent is selected from the
- 2 group consisting of common Grignard reagents R"MgX, alkalihalides, zinc compounds
- 3 comprising ZnI<sub>2</sub>, ZnBr<sub>2</sub>, ZnCl<sub>2</sub>, and ZnF<sub>2</sub>, aluminum compounds comprising Al<sub>2</sub>H<sub>6</sub>, LiAlH<sub>4</sub>,
- 4 AlI<sub>3</sub>, AlBr<sub>3</sub>, AlCl<sub>3</sub>, and AlF<sub>3</sub>, and boron compounds comprising R"B(OH)<sub>2</sub>, BI<sub>3</sub>, BBr<sub>3</sub>, BCl<sub>3</sub>,
- 5 and BF<sub>3</sub>, where R" represents an organic substituent and X' represents an inorganic substituent.
- 1 46. (Twice amended) A process of converting a plurality of POSS fragments into a POSS
- 2 compound, comprising:
- mixing an effective amount of a base with the plurality of POSS fragments in a solvent to
- 4 produce a basic reaction mixture, the base reacting with the POSS fragments to produce the
- 5 POSS compound,

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6 wherein the POSS fragments have the formula  $(RSiO_{1.5})_m(RXSiO_{1.0})_n$  and contain from 1

- to 7 silicon atoms and no more than 3 rings, and the POSS compound is selected from the group
- 8 consisting of homoleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_n]_{\Sigma\#}$ ,
- 9 heteroleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_m(R'SiO_{1.5})_n]_{\Sigma\#}$
- 10 functionalized homoleptic nanostructure compounds having the formula
- [(RSiO<sub>1.5</sub>)<sub>m</sub>(RXSiO<sub>1.0</sub>)<sub>n</sub>] $_{\Sigma^{\#}}$ , functionalized heteroleptic nanostructure compounds having the
- formula  $[(RSiO_{1.5})_m(R'SiO_{1.5})_n(RXSiO_{1.0})_p]_{\Sigma\#}$ , and expanded POSS fragments having the
- formula (RSiO<sub>1.5</sub>)<sub>m</sub>(RXSiO<sub>1.0</sub>)<sub>n</sub>, where R and R' each represents an organic substituent, X
- 14 represents a functionality substituent, m, n and p represent the stoichiometry of the formula,  $\sum$
- 15 indicates nanostructure, and # represents the number of silicon atoms contained within the

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16 nanostructure.

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- 1 53. (Once amended) The process of claim 52, wherein the base is selected from the group
- 2 consisting of hydroxide [OH], organic alkoxides [R"O], carboxylates [R"COO], amides
- 3 [R"NH], carboxamides [R"C(O)NR"], carbanions [R"], carbonate [CO<sub>3</sub>]<sup>-2</sup>, sulfate [SO<sub>4</sub>]<sup>-2</sup>,
- 4 phosphate  $[PO_4]^{-3}$ , biphosphate  $[HPO_4]^{-2}$ , phosphorus ylides  $[R''_4P]^{-1}$ , nitrate  $[NO_3]^{-1}$ , borate
- [B(OH)<sub>4</sub>], cyanate [OCN], fluoride [F], hypochlorite [OCl], silicate [SiO<sub>4</sub>]<sup>-4</sup>, stannate [SnO<sub>4</sub>]<sup>-4</sup>,
- basic metal oxides comprising Al<sub>2</sub>O<sub>3</sub>, CaO, and ZnO, amines R"<sub>3</sub>N and amine oxides R"<sub>3</sub>NO,
- 7 and organometallics comprising R"Li, R"<sub>2</sub>Zn, R"<sub>2</sub>Mg, and R"MgX', where R" represents an
- 8 organic substituent and multiple organic substituents need not be identical, and X' represents an
- 9 inorganic substituent.
- 1 58. (Once amended) The process of claim 47, wherein the co-reagent is selected from the
- 2 group consisting of common Grignard reagents R"MgX, alkalihalides, zinc compounds
- 3 comprising ZnI<sub>2</sub>, ZnBr<sub>2</sub>, ZnCl<sub>2</sub>, and ZnF<sub>2</sub>, aluminum compounds comprising Al<sub>2</sub>H<sub>6</sub>, LiAlH<sub>4</sub>,
- 4 AlI<sub>3</sub>, AlBr<sub>3</sub>, AlCl<sub>3</sub>, and AlF<sub>3</sub>, and boron compounds comprising R"B(OH)<sub>2</sub>, BI<sub>3</sub>, BBr<sub>3</sub>, BCl<sub>3</sub>,
- 5 and BF<sub>3</sub>, where R" represents an organic substituent and X' represents an inorganic substituent.
- 1 67. (Once amended) The process of claim 66, wherein the base is selected from the group
- 2 consisting of hydroxide [OH], organic alkoxides [R"O], carboxylates [R"COO], amides
- 3 [R"NH], carboxamides [R"C(O)NR"], carbanions [R"], carbonate [CO<sub>3</sub>], sulfate [SO<sub>4</sub>],
- 4 phosphate [PO<sub>4</sub>]<sup>-3</sup>, biphosphate [HPO<sub>4</sub>]<sup>-2</sup>, phosphorus ylides [R"<sub>4</sub>P], nitrate [NO<sub>3</sub>], borate
- 5 [B(OH)<sub>4</sub>], cyanate [OCN], fluoride [F], hypochlorite [OCl], silicate [SiO<sub>4</sub>]<sup>-4</sup>, stannate [SnO<sub>4</sub>]<sup>-4</sup>,
- 6 basic metal oxides comprising Al<sub>2</sub>O<sub>3</sub>, CaO, and ZnO, amines R"<sub>3</sub>N and amine oxides R"<sub>3</sub>NO,
- 7 and organometallics comprising R"Li, R"<sub>2</sub>Zn, R"<sub>2</sub>Mg, and R"MgX', where R" represents an
- 8 organic substituent and multiple organic substituents need not be identical, and X' represents an
- 9 inorganic substituent.

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- (Once amended) The process of claim 71, wherein the co-reagent is selected from the
  - 2 group consisting of common Grignard reagents R"MgX, alkalihalides, zinc compounds

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3 comprising ZnI<sub>2</sub>, ZnBr<sub>2</sub>, ZnCl<sub>2</sub>, and ZnF<sub>2</sub>, aluminum compounds comprising Al<sub>2</sub>H<sub>6</sub>, LiAlH<sub>4</sub>,

4 AlI<sub>3</sub>, AlBr<sub>3</sub>, AlCl<sub>3</sub>, and AlF<sub>3</sub>, and boron compounds comprising R"B(OH)<sub>2</sub>, BI<sub>3</sub>, BBr<sub>3</sub>, BCl<sub>3</sub>,

5 and BF<sub>3</sub>, where R" represents an organic substituent and X' represents an inorganic substituent.

1 86. (Twice amended) A process of converting an unfunctionalized POSS nanostructure compound into a functionalized POSS nanostructure compound, comprising:

mixing an effective amount of a base with the unfunctionalized POSS nanostructure compound in a solvent to produce a basic reaction mixture, the base reacting with the unfunctionalized POSS nanostructure compound to produce the functionalized POSS nanostructure compound,

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wherein the unfunctionalized POSS nanostructure compound is selected from the group consisting of homoleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_n]_{\Sigma^{\#}}$  and heteroleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_m(R'SiO_{1.5})_n]_{\Sigma^{\#}}$ , and the functionalized POSS nanostructure compound is selected from the group consisting of functionalized homoleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma^{\#}}$  and functionalized heteroleptic nanostructure compounds having the formula  $[(RSiO_{1.5})_m(RXSiO_{1.5})_n(RXSiO_{1.0})_p]_{\Sigma^{\#}}$ , where R and R' each represents an organic substituent, X represents a functionality substituent, m, n and p represent the stoichiometry of the formula,  $\Sigma$  indicates nanostructure, and  $\pi$  represents the number of silicon atoms contained within the nanostructure.

1 93. (Once amended) The process of claim 92, wherein the base is selected from the group

2 consisting of hydroxide [OH], organic alkoxides [R"O], carboxylates [R"COO], amides

3 [R"NH], carboxamides [R"C(O)NR"], carbanions [R"], carbonate [CO<sub>3</sub>], sulfate [SO<sub>4</sub>],

4 phosphate [PO<sub>4</sub>]<sup>-3</sup>, biphosphate [HPO<sub>4</sub>]<sup>-2</sup>, phosphorus ylides [R"<sub>4</sub>P]<sup>-</sup>, nitrate [NO<sub>3</sub>]<sup>-</sup>, borate

5 [B(OH)<sub>4</sub>], cyanate [OCN], fluoride [F], hypochlorite [OCl], silicate [SiO<sub>4</sub>], stannate [SnO<sub>4</sub>],

basic metal oxides comprising Al<sub>2</sub>O<sub>3</sub>, CaO, and ZnO, amines R"<sub>3</sub>N and amine oxides R"<sub>3</sub>NO,

7 and organometallics comprising R"Li, R"<sub>2</sub>Zn, R"<sub>2</sub>Mg, and R"MgX', where R" represents an

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organic substituent and multiple organic substituents need not be identical, and X' represents an

9 inorganic substituent.

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- 1 97. (Twice amended) The process of claim 86, further comprising mixing a co-reagent with
- 2 the base and the unfunctionalized POSS nanostructure compound in the solvent.

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- 1 98. (Once amended) The process of claim 97, wherein the co-reagent is selected from the
- 2 group consisting of common Grignard reagents R"MgX, alkalihalides, zinc compounds
- 3 comprising ZnI<sub>2</sub>, ZnBr<sub>2</sub>, ZnCl<sub>2</sub>, and ZnF<sub>2</sub>, aluminum compounds comprising Al<sub>2</sub>H<sub>6</sub>, LiAlH<sub>4</sub>,
- 4 AlI<sub>3</sub>, AlBr<sub>3</sub>, AlCl<sub>3</sub>, and AlF<sub>3</sub>, and boron compounds comprising R"B(OH)<sub>2</sub>, BI<sub>3</sub>, BBr<sub>3</sub>, BCl<sub>3</sub>,
- 5 and BF<sub>3</sub>, where R" represents an organic substituent and X' represents an inorganic substituent.
- 1 114. (Once amended) A process of converting a polymeric silsesquioxane into a POSS nanostructure compound, comprising:
  - mixing an effective amount of a base with the polymeric silsesquioxane in a solvent to produce a basic reaction mixture, the base reacting with the polymeric silsesquioxane to produce the POSS nanostructure compound,

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- wherein the polymeric silsesquioxane has the formula  $[RSiO_{1.5}]_{\infty}$ , and the POSS nanostructure compound is  $[(RSiO_{1.5})_4(RXSiO_{1.0})_3]_{\Sigma7}$ , where R represents an organic substituent,
- 8 X represents a functionality substituent, ∞ represents the degree of polymerization and is a
- 9 number greater than or equal to 1, m, n and p represent the stoichiometry of the formula,  $\sum$
- 10 indicates nanostructure, and # represents the number of silicon atoms contained within the
- 11 nanostructure.

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- 1 128. (Twice amended) A compound having the formula  $[(XSiO_{1.5})_n]_{\Sigma^{\#}}$ , where X represents a
- 2 functionality substituent, n represents the stoichiometry of the formula,  $\sum$  indicates
- 3 nanostructure, and # represents the number of silicon atoms contained within the nanostructure.